

a cylindrical discharge electrode fashioned so as to enclose said plasma generation region;

first high-frequency power application means for applying high-frequency electric power to said discharge electrode;

magnetic force line forming means that form magnetic force in said plasma generation region;

two walls, formed of a substance exhibiting electrical conductivity, and positioned so as to sandwich said plasma generation region between them, in dimension of said center axis of said discharge electrode, for defining the scope of said plasma generation region in said center axial dimension, wherein a substrate is located between said two walls; and

second high-frequency electric power application means for applying high-frequency electric power to at least one of said two walls.

REMARKS

By this Amendment, claims 1 and 16 are amended to further clarify the rejected subject matter. Reconsideration in view of the above amendment and the following remarks is respectfully requested. Claims 1-16 are pending in this application.

I. PRIOR ART REJECTIONS

- A. Applicants Traverse the Rejection Under
35 U.S.C. §103(a) of Claims 1, 2, 4 and 6 Over Kisakibaru
et al. in view of Watanabe, Nakayama et al. and Saito et al.

The Office Action rejected claims 1, 2, 4 and 6 under 35 U.S.C. §103(a) as being unpatentable over Kisakibaru et al. (U.S. Patent No. 5,431,769, hereinafter "Kisakibaru") in view of Watanabe (U.S. Patent No. 5,073,241), Nakayama et al. (U.S. Patent No. 4,894,254, hereinafter "Nakayama") and Saito et al. (U.S. Patent No. 5,587,205, hereinafter "Saito").